

Title (en)
Negative resist composition

Title (de)
Negativ arbeitende Resistzusammensetzung

Title (fr)
Composition pour réserve de type négatif

Publication
EP 1193555 A1 20020403 (EN)

Application
EP 01120664 A 20010831

Priority
JP 2000263815 A 20000831

Abstract (en)
A negative resist composition comprises: (A) an alkali-soluble resin; (B) a compound capable of generating an acid upon irradiation with a radiation; (C) a crosslinking agent capable of crosslinking by the action of an acid; and (D) a solvent mixture containing: at least one solvent selected from the group A below; and at least one selected from the group consisting of the group B below and the group C below: group A: a propylene glycol monoalkyl ether carboxylate; group B: a propylene glycol monoalkyl ether, an alkyl lactate, an acetic ester, a chain ketone and an alkyl alkoxypropionate; group C: a gamma -butyrolactone, an ethylene carbonate and a propylene carbonate.

IPC 1-7
G03F 7/004; **G03F 7/038**

IPC 8 full level
G03F 7/038 (2006.01); **C07C 25/18** (2006.01); **C07C 39/15** (2006.01); **C07C 43/178** (2006.01); **C07C 309/39** (2006.01); **C07C 381/12** (2006.01); **G03F 7/004** (2006.01); **H01L 21/027** (2006.01)

CPC (source: EP KR US)
G03F 7/004 (2013.01 - KR); **G03F 7/0045** (2013.01 - KR); **G03F 7/0047** (2013.01 - KR); **G03F 7/0048** (2013.01 - EP US); **G03F 7/038** (2013.01 - EP KR US); **G03F 7/0382** (2013.01 - KR); **Y10S 430/115** (2013.01 - EP US); **Y10S 430/143** (2013.01 - EP US); **Y10S 430/167** (2013.01 - EP US)

Citation (search report)
• [XP] EP 1117002 A1 20010718 - FUJI PHOTO FILM CO LTD [JP]
• [X] EP 0634696 A1 19950118 - JAPAN SYNTHETIC RUBBER CO LTD [JP]
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Citation (examination)
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Designated contracting state (EPC)
BE DE

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EP 1193555 A1 20020403; JP 2002148806 A 20020522; JP 4194259 B2 20081210; KR 100851842 B1 20080813; KR 100895455 B1 20090507; KR 20020018584 A 20020308; KR 20080053455 A 20080613; TW 536662 B 20030611; US 2002061462 A1 20020523; US 6887645 B2 20050503

DOCDB simple family (application)
EP 01120664 A 20010831; JP 2001264111 A 20010831; KR 20010053138 A 20010831; KR 20080051672 A 20080602; TW 90121630 A 20010831; US 94276801 A 20010831